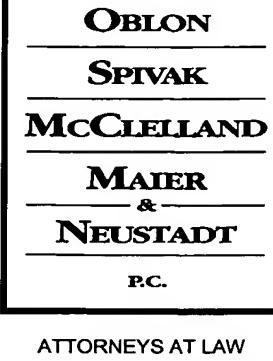




Docket No.: 250312US26YA

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313



RE: Application Serial No.: 10/813,390

Applicants: Marcel GAUDET, et al.

Filing Date: March 31, 2004

For: SYSTEM AND METHOD OF REMOVING
CHAMBER RESIDUES FROM A PLASMA
PROCESSING SYSTEM IN A DRY CLEANING
PROCESS

Group Art Unit: 1762

Examiner: Kelly M. STOUFFER

SIR:

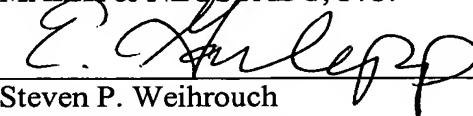
Attached hereto for filing are the following papers:

Statement of Substance of Interview

Our credit card payment form in the amount of \$0.00 is attached covering any required fees. In the event any variance exists between the amount enclosed and the Patent Office charges for filing the above-noted documents, including any fees required under 37 C.F.R. 1.136 for any necessary Extension of Time to make the filing of the attached documents timely, please charge or credit the difference to our Deposit Account No. 15-0030. Further, if these papers are not considered timely filed, then a petition is hereby made under 37 C.F.R. 1.136 for the necessary extension of time. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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DOCKET NO: 250312US26YA



IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF

MARCEL GAUDET, ET AL.

: EXAMINER: KELLY M. STOUFFER

SERIAL NO: 10/813,390

:

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: GROUP ART UNIT: 1762

FOR: SYSTEM AND METHOD OF
REMOVING CHAMBER RESIDUES
FROM A PLASMA PROCESSING
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PROCESS

STATEMENT OF SUBSTANCE OF INTERVIEW

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

SIR:

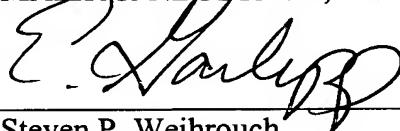
Applicants wish to thank the Examiner for the interview granted Applicants' representative on November 29, 2006, at which time the outstanding rejections of Claims 1-28 were discussed. During the interview, the following is a summary of what was discussed:

- Claim 1 makes clear that the method applies to cleaning residues from a plasma processing system. Further a gas containing carbon and oxygen is introduced into the process chamber and a plasma is generated from this gas. The plasma constituents then react with the chamber residue to form a volatile reaction product and the reaction product is exhausted thereby removing the contaminant from the chamber.
- The invention disclosed in Jung et al. is not directed to cleaning a chamber residue at all, but rather is directed to cleaning a workpiece, such as a PCB.

- Paragraph 8 of June et al. does not disclose introducing a process gas including a gas containing carbon and oxygen into a process chamber of the plasma processing system and generating a plasma from the process gas as required by Applicants' independent Claims 1, 27 and 28.
- Even assuming that the detailed description of Jung et al. relates to a method of cleaning a chamber of a plasma processing system, Jung et al. still does not disclose introducing a process gas including a gas containing carbon and oxygen as required by Applicants' independent claims.

Respectfully submitted,

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(OSMMN 06/04)